UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Hui Lin Chang

Serial No.: 10/696,254

Filed:

October 29, 2003

For:

Insulating Layer Having Decreased Dielectric Constant and Increased

*\text{\tin}\text{\tetx{\text{\tetx{\text{\texi}\text{\text{\text{\texi}\text{\text{\text{\text{\texi}\text{\text{\text{\texi}\text{\text{\text{\text{\text{\ticr{\texi}\text{\text{\texi}\text{\text{\text{\text{\text{\text{* 

Conf. No.:

Customer No.

7076

42717

Docket No.: 24061.36 (2002-0939)

Hardness

**TRANSMITTAL** 

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified patent application is:

- 1. Power of Attorney for Patent Application with copy of executed Assignment;
- 2. This transmittal; and
- 3. Return receipt postcard.

Applicant believes no fee is due. However, the Director is authorized to charge any deficiency fees or credit any overpayments to Deposit Account No. 08-1394 of Haynes and Boone, LLP.

Respectfully submitted,

David M. O'Dell

Reg. No. 42,044

HAYNES AND BOONE, LLP 901 Main Street, Suite 3100

8-25-05

Dallas, Texas 75202-3789 Telephone: 972-739-8635

Facsimile: 214-200-0853

Customer Number: 42717

#### CERTIFICATE OF FACSIMILE

I hereby certify that this correspondence is being sent via facsimile, 703-308-7751, addressed to the Office of Initial Patent Examination, Commissioner For Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on the date indicated below:



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re applic	ation of:	§	Docket No.:	24061.36		
	Hui Lin Chang	§		(TSMC2002-0939)		
		§	_	14.41.1 #		
Serial No.:	10/696,254	§	Customer No.:	42717		
		§		0011		
Filed:	October 29, 2003	§	Group Art Unit:	2811		
	_	§				
Fот:	INSULATING LAYER HAVING	§	Examiner:	To Be Determined		
	DECREASED DIELECTRIC	Ş				
	CONSTANT AND INCREASED	8				

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

HARDNESS

#### POWER OF ATTORNEY FOR PATENT APPLICATION

As a representative of the Assignce, Taiwan Semiconductor Manufacturing, Co. Ltd., I hereby appoint the following attorneys to prosecute the above-identified application and to transact all business in the United States Patent and Trademark Office in connection therewith:

Practitioners associated with the Customer Number

42717

Please direct all correspondence and telephone calls to the address associated with the above-mentioned Customer Number.

The undersigned representative for the Assignee certifies that the assignee is the assignee of the entire right, title and interest in the above-identified patent application. A copy of the assignment or other documents in the chain of title are attached.

Executed the	:	_day of .	, 20	005.			
			 		 . 4-7	 	

Taiwan Semiconductor Manufacturing Company, Ltd.

Chien Wei Chou Director, IP Division

ı

Patent / Docket No.: 24061.36/TSMC2002-0939

Customer No. 27683

### ASSIGNMENT

WHEREAS, we

(1) Hui Lin Chang

of Taiwan, R.O.C.

have invented certain improvements in

# INSULATING LAYER HAVING DECREASED DIELECTRIC CONSTANT AND INCREASED HARDNESS

for which we have executed an application for Letters Patent of the United States of America, of even date herewith; and

WHEREAS, Taiwan Semiconductor Manufacturing Company, Ltd., ("TSMC"), No. 6, Li-Hsin Rd. 6, Science-Based Industrial Park Hsin-Chu, Taiwan 300-77, Republic of China is desirous of obtaining the entire right, title, and interest in, to and under the said invention and the said application in the United States of America and in any and all countries foreign thereto;

NOW, THEREFORE, for One Dollar (\$1.00) and other good and valuable consideration, the receipt and sufficiency of which is hereby acknowledged, and other good and valuable consideration, we have sold, assigned, transferred and set over, and by these presents do hereby sell, assign, transfer and set over, unto the said TSMC, its successors, legal representatives, and assigns, the entire right, title, and interest in, to and under the said invention, and the said application, and all divisional, renewal, substitutional, and continuing applications thereof, and all Letters Patent of the United States of America which may be granted thereon and all reissues and extensions thereof, and all applications for Letters Patent which may be filed for said invention in any country or countries foreign to the United States of America, and all extensions, renewals, and reissues thereof, and all prior patents and patent applications from which a filing priority of the above-described patent application may be obtained, including the right to collect past damages; and we hereby authorize and request the Commissioner of Patents of the United States of America, and any official of any country or countries foreign to the United States of America, whose duty it is to issue patents on applications as aforesaid, to issue all Letters Patent for said invention to the said TSMC, its successors, legal representatives and assigns, in accordance with the terms of this instrument.

AND WE HEREBY covenant that we have full right to convey the entire interest herein assigned, and that we have not executed, and will not execute, any agreement in conflict herewith.

AND WE HEREBY further covenant and agree that we will communicate to said TSMC, its successors, legal representatives and assigns, any facts known to us respecting said invention, and testify in any legal proceedings, sign all lawful papers, execute all divisional, renewal, substitutional, continuing, and reissue applications, make all rightful declarations and/or oaths and generally do everything possible to aid the said TSMC, its successors, legal representatives and assigns, to obtain and enforce proper patent protection for said invention in all countries.

Patent / Docket No.: 24061.36/TSMC2002-0939 Customer No. 27683

First Inventor Name: HULThehap	Hui Lin Chang
First Inventor Name: HUILTRehaf Residence Address: 50 Ta-Hsueh 10 ad, 10 F-4, HSTACHU 36050	, Tailvan
Dated: /0/03/03	Huitin Charg
	Inventor Signature
Dated: (0/03/03)	
	Witness Signature
	Witness Name: Ta. To. Cho.